

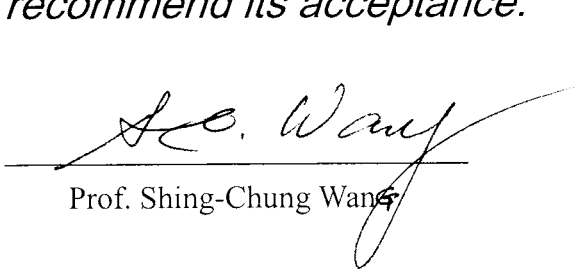
Department of Materials Science and Engineering
National Chiao Tung University

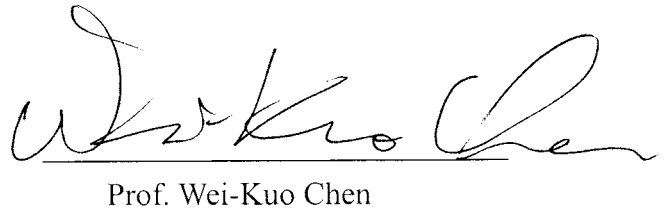
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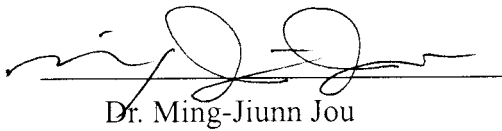
May 27, 2004

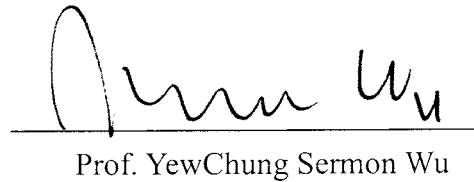
We have carefully read the dissertation entitled

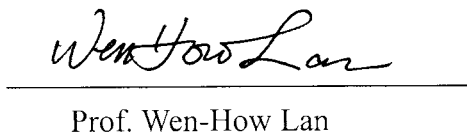
*Material Characterizations and Process Development of
WN_x T-gate AlGa_N/Ga_N High Electron Mobility
Transistor for High Temperature Applications*
*submitted by CHAO-YI FANG in partial fulfillment of the
requirement of the degree of DOCTOR OF PHILOSOPHY and
recommend its acceptance.*



Prof. Shing-Chung Wang


Prof. Wei-Kuo Chen

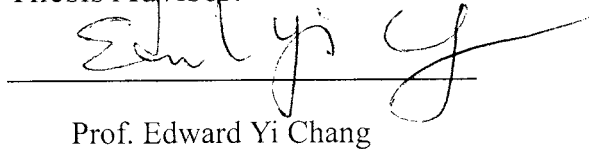

Dr. Ming-Jiunn Jou

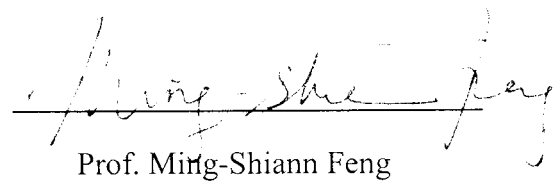

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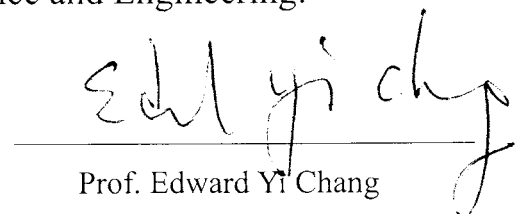

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